



Course Title and Code Number:
 Semiconductor Devices (EE336)
 Third Year (Communications and Electronics)
 Time Allowed: 90 Mins

اسم المقرر والرقم الكودي له:
 النبايط شبه الموصله (EE336)
 السنة الدراسية الثالثة (اتصالات و الكترونيات)
 الزمن: ٩٠ دقيقة

Info and Equation Sheets Are Allowed:

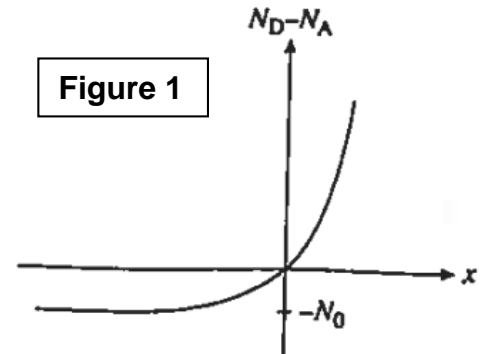
Attempt All Questions:

(45 marks)

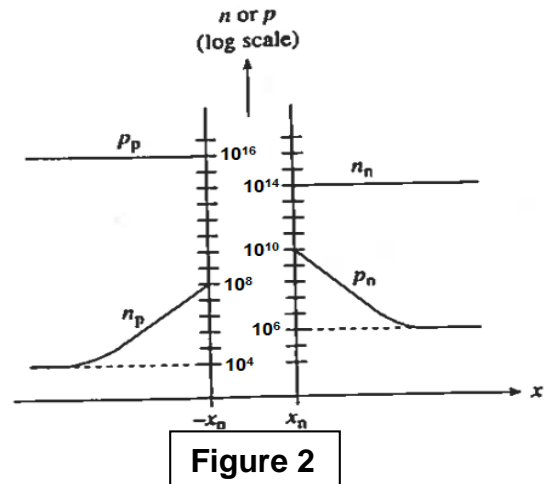
Question 1:

(15 marks)

- a) A pn junction diode has the doping profile sketched in Figure 1. Mathematically $N_D - N_A = N_0(e^{\alpha x} - 1)$, where N_0 and α are constants.
- Give a concise statement of the depletion approximation.
 - Invoking the depletion approximation, sketch the charge density inside the diode.
 - Establish an expression for the electric field $\mathcal{E}(x)$ inside the depletion region.



- b) Figure 2 is a dimensioned plot of the steady state carrier concentrations inside a step pn junction diode maintained at room temperature.
- Is the diode forward or reverse biased? Do low level injection conditions prevail in the quasineutral regions of the diode? Explain how you arrived at your answer.
 - What are the p-side and n-side doping concentrations?
 - Determine the diode current I and applied voltage V_A assuming $I_0 = 100nA$.



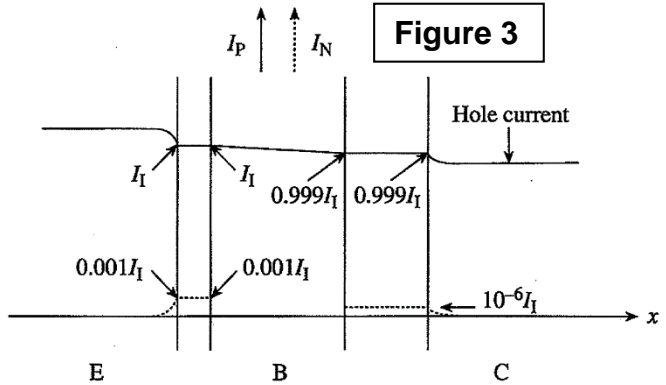
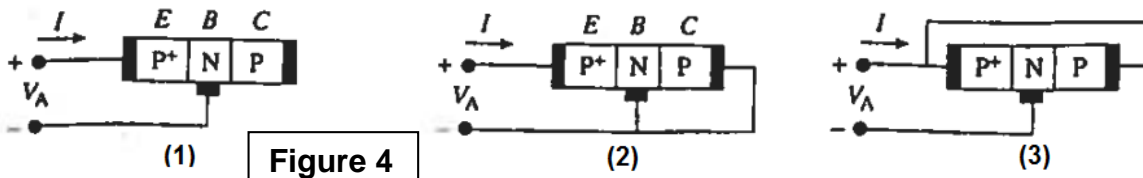
Question 2:

(15 marks)

- a) The doping profile inside the semiconductor component of an MS diode is linearly graded; i.e., $N_D(x) = ax$.
- Derive solution for $\rho(x)$, $\mathcal{E}(x)$, $V(x)$, and W inside the semiconductor.
 - Indicate how V_{bi} is to be determined and computed.
 - Establish an expression for the junction depletion region capacitance.
- b) The electron and hole currents inside a pnp BJT biased in the active mode are plotted in Figure 3. All the currents are referenced to I_1 , the hole current injected into the base. Determine:
- The emitter efficiency (γ), the base transport factor (α_T), the common emitter d.c. current gain (β_{dc}).
 - The base current (I_B).

III. Derive the $I-V_A$ relationship for the above transistor connected in the configurations shown in Figure 4 by appropriately using the Ebers-Moll model. The current I should be expressed only in terms of V_A and the Ebers-Moll parameters.

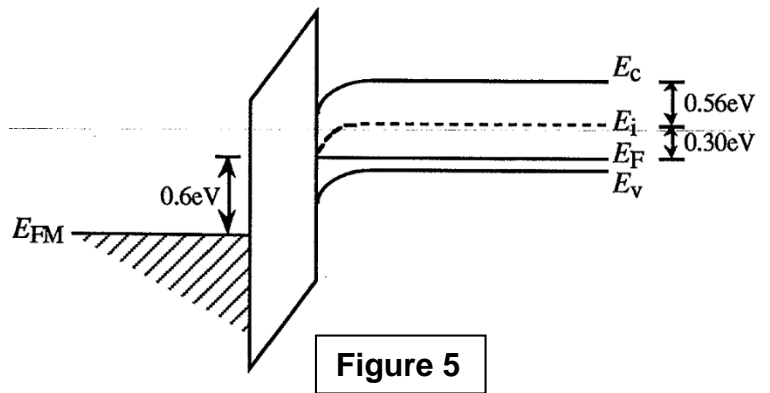
IV. Develop expressions for $\Delta p_B(0)/\Delta p_{B0}$ and $\Delta p_B(W)/\Delta p_{B0}$ in terms of V_A and the Ebers-Moll parameters.



Question 3:

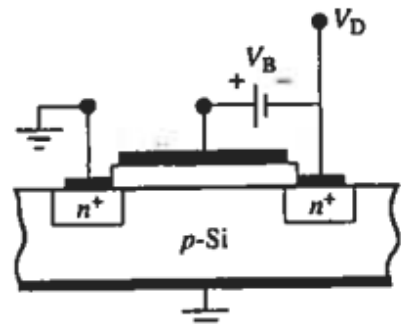
(15 marks)

a) The energy band diagram for an ideal $x_o = 0.2\mu\text{m}$ MOS-C operated at $T = 300^\circ\text{K}$ is sketched in Figure 5. Note that the applied gate voltage causes band bending in the semiconductor such that $E_F = E_i$ at the Si-SiO₂ interface. Invoke the delta-depletion approximation as required in answering the questions that follow.



- I. Sketch ρ , \mathcal{E} , V inside the semiconductor as a function of position.
- II. What is the electron concentration at the Si-SiO₂ interface?
- III. Calculate N_D , ϕ_s , V_G , and the voltage drop ($\Delta\phi_{ox}$) across the oxide at the pictured bias point.
- IV. What is the normalized small-signal capacitance, C/C_0 , of the MOS-C at the pictured bias point?

b) Suppose a battery $V_B \geq 0$ is connected between the gate and drain of an ideal n-channel MOSFET as pictured in Figure 6. Using the square law results,



- I. Sketch I_D versus V_D ($V_D \geq 0$) for $V_B = V_T/2, 2V_T$;
- II. Sketch I_D versus V_B ($0 \geq V_B \geq 5V$) for $V_D=0, 5V$.

Good Luck

Examiner: **Dr. Mohammed Morsy**